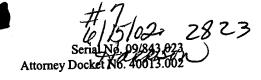
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in the united states patent and trademark office

In re Patent Application:
Becky Losee

Serial No.: 09/843,023

Filed: April 26, 2001

For: METHODS FOR ETCHING SILICON

**TRENCHES** 

Confirmation No. 7229

Group Art Unit: 2823

Examiner: J. Muldonado

RECEIVED TOO TOO

Commissioner for Patents Washington, D.C. 20231

Box Non-Final Response

Sir:

## RESPONSE TO RESTRICTION REQUIREMENT

In response to the Office Action dated May 3, 2002, Applicant requests reconsideration of the restriction requirement and examination of all claims in light of the following remarks.

## Remarks

The Office has required restriction to one of the following groups of inventions under 35 U.S.C. § 121:

Group I: claims 1-30, drawn to a method to form a semiconductor device, classified in class 438, subclass 709; and

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D. C. 20231, on this 16<sup>th</sup> Day of May 2002.

Signed

D-4-4

16,2002

5/16/2002